
**Surface chemical analysis — Chemical
methods for the collection of elements
from the surface of silicon-wafer working
reference materials and their
determination by total-reflection X-ray
fluorescence (TXRF) spectroscopy**

*Analyse chimique des surfaces — Méthodes chimiques pour collecter
les éléments analysés de tranches de silicium comme matériaux de
référence pour l'analyse par spectroscopie de fluorescence X en
réflexion totale (TXRF)*



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